

LiPON Thin Film Deposition for 3D Lithium Microbatteries Mila'na Jones, Anantharamulu Navulla, and Lamartine Meda Department of Chemistry, Xavier University of LA, New Orleans, LA, 70125

Introduction In recent years there has been the realization that improved battery performance can be achieved by moving from the conventional 2-D batteries (Fig 1) to 3-D architectures (Fig. 2).



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<u>Project Goal</u>: Use RF magnetron sputtering processes to grow LiPON thin films on nanorods or nanowires (see Fig. 3 below).



Schematic of LiPON-coated C anode or $Li_{x}MnO_{2-y}$ cathode nanorod arrays. (Meda and Yûshin (Ûnpublished)



 WO_3 deposited by vapor solid (VS) growth method. L. Meda and C. White (Unpublished)

Fig. 3: (a) Illustration of cathode and anode materials coated with LiPON and (b) WO₃ nanowires.

<u>Materials and method</u> Lipon thin films deposited by the RF-magnetron sputtering process (Fig. 4) on 3000 Å of Au current collector.



Fig. 4. (a) Dual magnetron sputtering system and (b) Inside the chamber

<u>LiPON Deposition Process</u>. The targets were sputtered in an environment of pure N_{2} , preset to a flow of 25 sccm. The RF power in the chamber was kept at a constant 100 W while sputtering the targets for 5 hours. Characterization Fig. 2









Fig. 5 Cross-section SEM Image of LiPON on Si with a growth rate of ~ 30 Å/min. Some pinhole-defects may be present but will be filled via electropolymerization.



XPS analysis of LiPON deposited by sputtering.

at%	Sputtering in Ar-N ₂
Li	25
Ρ	17
0	49
Ν	4
С	4.8





AC Impedance Fig. 8 shows the complex impedance of Lipon. Lipon was sandwiched between Au current collectors (Au area (A) ~ 0.06 cm²). Lipon thickness (*d*) was ~ 1mm and ionic conductivity was 2.2 x 10⁻⁸⁸ ohm⁻¹cm⁻¹.



<u>Conclusion</u>: Lipon thin films were deposited by magnetron sputtering with ionic conductivity approximately 2.2 x 10⁻⁸ ohm⁻¹ cm^{-1} .

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